

**A) Amendments to the Claims:**

Claim 1 (currently amended). A vacuum evaporation deposition method of the winding type in which under an atmosphere of reduced pressure, an insulating material base film is continuously fed out, cooled in close contact with a cooling roller and metal is evaporated onto said insulating material base film to deposit a metal film thereon, the method characterized in that:

before the deposition of the metal film, forming a mask pattern by depositing an oil pattern on a surface of the insulating material base film for defining a deposition region for the metal film, and charging said insulating material base film whereby said insulating material base film is thereby closely contacted with said cooling roller ~~by charging said insulating material base film, and;~~

after the deposition of the metal film, applying a voltage between said metal film and said cooling roller whereby said insulating material base film is closely contacted with said cooling roller ~~by applying a voltage between said metal film and said cooling roller, and plasma-bombarding said insulating material base film for thereby removing electrical charge on said insulating base film prior to take-up winding.~~

Claim 2 (previously presented). A vacuum evaporation deposition method of the winding type according to claim 1, in which in the step of charging said insulating material base film is performed with charged particles irradiated onto the running insulating material base film while being scanned in the width direction of said insulating material base film.

Claim 3 (previously presented). A vacuum evaporation deposition method of the winding type according to claim 2, in which said charged particles are irradiated at a time when said insulating material base film is contacted with said cooling roller.

Claim 4 (previously presented). A vacuum evaporation deposition method of the winding type according to claim 1, in which in the step of applying the voltage between the metal film and said cooling roller, a DC voltage is applied between an auxiliary roller for guiding said insulating material base film with said metal film deposited thereon and said cooling roller.

Claim 5 (previously presented). A vacuum evaporation deposition method of the winding type according to claim 4, in which the step of applying the voltage between the metal film and said cooling roller includes a step of measuring a surface potential of said metal film and another step of so controlling the applying voltage as to place said surface potential within a predetermined range.

Claim 6 (canceled).

Claim 7 (canceled).

Claim 8 (currently amended). A vacuum evaporation deposition apparatus of the winding type in which there are provided in a vacuum chamber, an unwinding roller for continuously feeding an insulating material base film, a winding roller for taking up said insulating material base film, a cooling roller for cooling said insulating material base film when in contact, said rollers arranged

between said unwinding roller and said winding roller, and an evaporation source for depositing a metal film on said insulating material base film arranged facing to said cooling roller, characterized in that said apparatus includes[,];

charged-particles irradiating means for irradiating charged particles onto said insulating material base film, said irradiating means arranged between said unwinding roller and said evaporation source[,];

an auxiliary roller for guiding said insulating material base film in contact with the deposited metal film, said auxiliary roller arranged between said winding roller and said cooling roller[, and];

voltage-applying means for applying a DC voltage between said auxiliary roller and said cooling roller[,];

mask pattern forming means for forming an oil pattern which defines a mask pattern of deposition regions for said metal film on said insulating material base film, said mask pattern forming means arranged between said unwinding roller and said charged-particles irradiating means;  
and

electricity removal means for removing electrical charge on said insulating material base film by plasma-bombarding, said electricity removal means arranged between said auxiliary roller and said winding roller.

Claim 9 (previously presented). A vacuum evaporation deposition apparatus of the winding type according to claim 8, in which there is provided detecting means for detecting a surface potential of said metal film deposited on said insulating material base film, said detecting means arranged between said cooling roller and said auxiliary roller, and controlling means for controlling the applying voltage of said voltage applying means on the basis of the detected output of said detecting means.

Claim 10 (previously presented). A vacuum evaporation deposition apparatus of the winding type according to claim 8, in which said charged-particles irradiating means is arranged facing to the peripheral surface of said cooling roller.

Claim 11 (canceled).

Claim 12 (canceled).